



Si Trench IGBTs and SiC MOSFETs: Automotive applications

Dr. Marina Antoniou, University of Warwick

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Background

- BA and MEng in Electrical and Information Engineering, University of Cambridge.
- PhD in Electrical Engineering, University of Cambridge.
- EPSRC and Commonwealth Trust Scholar

- Associate Professor, University of Warwick
- Royal Society Dorothy Hodgkin Fellow (2017-2024)
- Chair of the IEEE Electron Device Society, Power Devices & ICs Committee
- Consulting experience and collaborations with major industrial organisations in power technologies: ABB, XFAB, AMS.

Outline



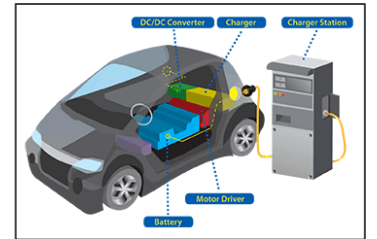
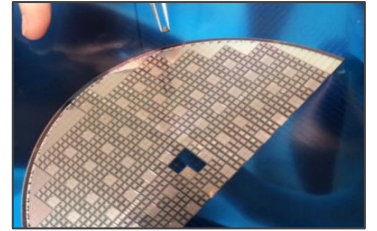
- Background
 - Requirements of Automotive Applications
 - Requirements of Power Device chips for Automotive applications
- Si Trench IGBT Technology
 - Narrow Mesa IGBTs
 - SJ IGBTs
 - RC IGBTs
- SiC MOSFETs
 - Main cell designs
 - Performance of SiC MOSFETs
 - Reliability
- Trends and Challenges

Background

Requirements to curb the global carbon emissions include:

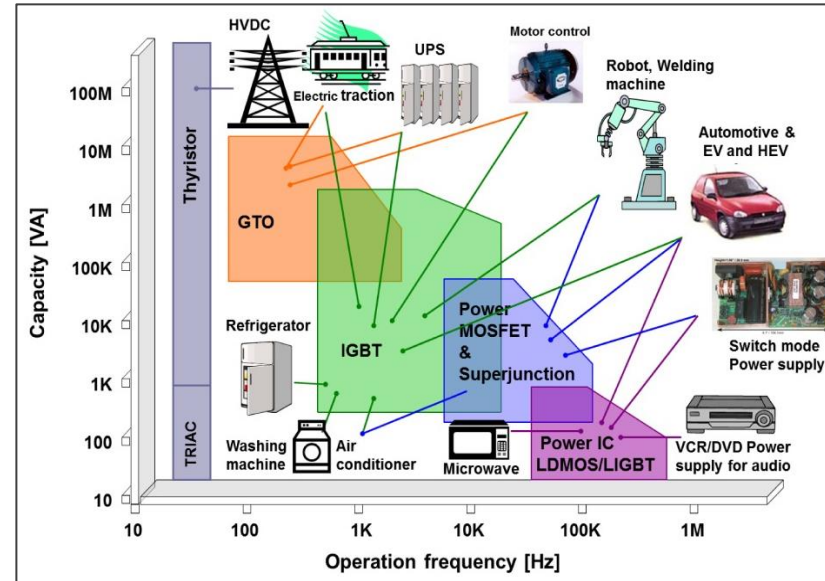
- Improved electrical efficiency
- More green electricity in the energy mix

The objectives can only be achieved with the utilization of energy efficient power semiconductor devices - building blocks of any power electronics technology.

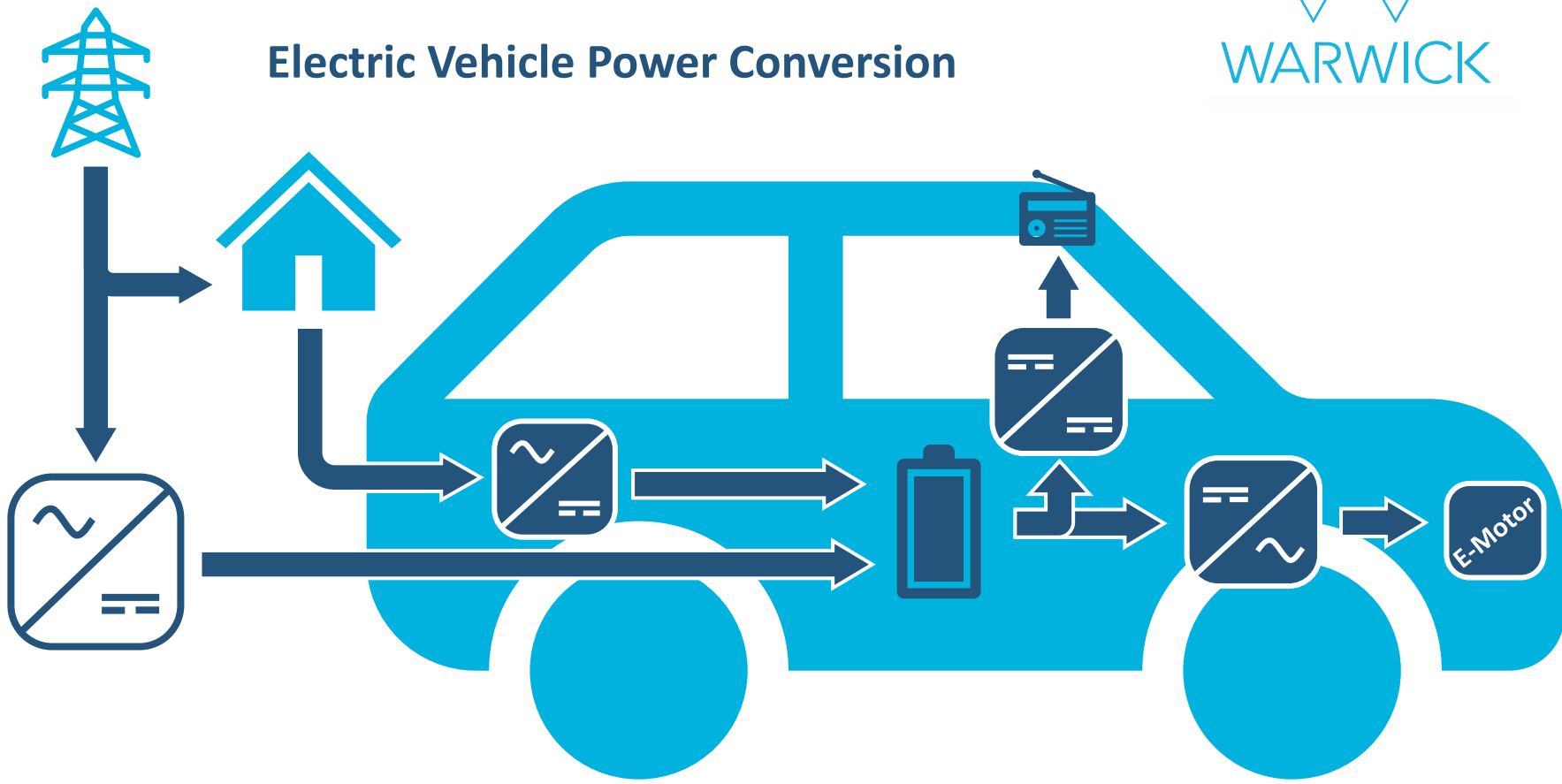


Background: Power Semiconductor Devices

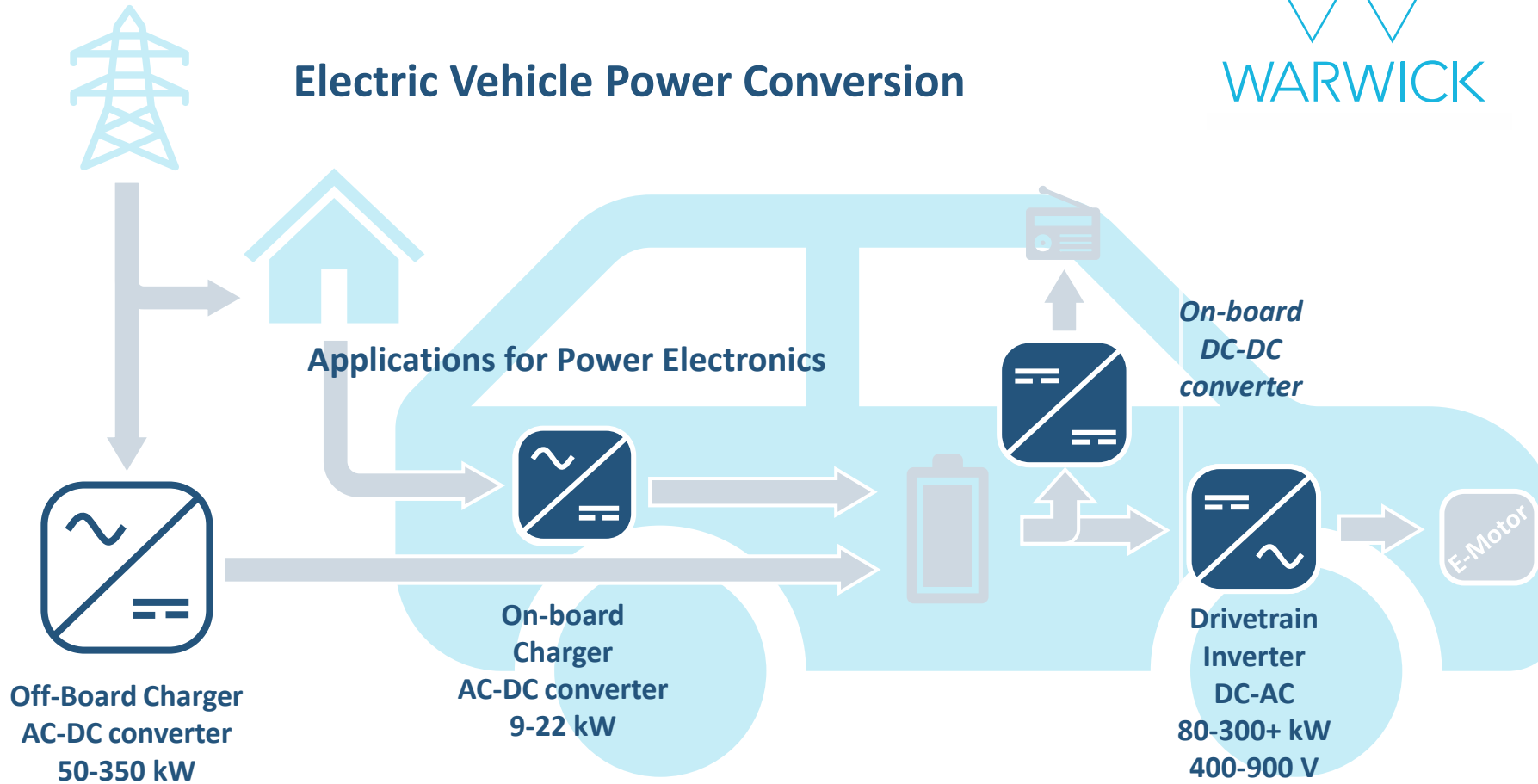
- They are key drivers and enablers in power electronics
- Used as a switches or rectifiers
- Achieve the supply of voltages and currents in a form that is optimally suited for each application with the smallest amount of energy loss.
- The global power semiconductor market is 40bn USD - every electronic device contains a power device.



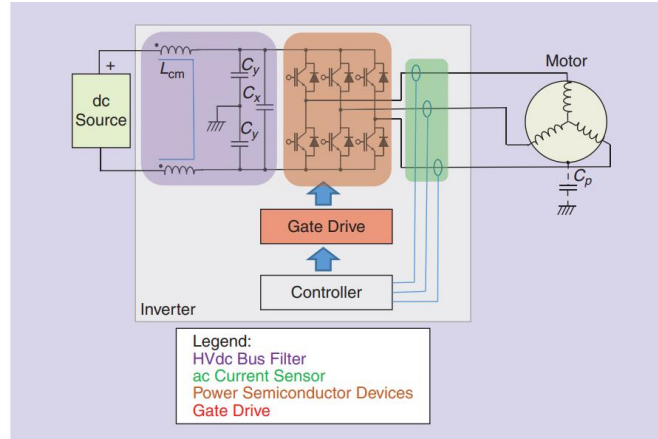
Electric Vehicle Power Conversion



Electric Vehicle Power Conversion



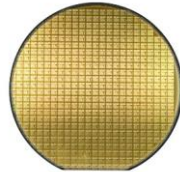
Automotive Applications Requirements



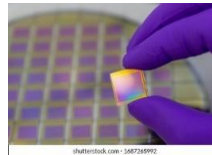
IEEE Electrification Magazine / March 2017



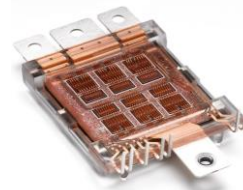
Monocrystalline ingot



Wafer



Chip die



Power module



Inverter

Automotive Applications Requirements

From the device perspective:

- High Power/ Efficiency
- Reliability (high vibrations, high humidity and ambient temperature variations)
- Cost
- Controllability and High Integration/Intelligence (integrated temperature and current sensors and shunt resistors, Drive-IC)

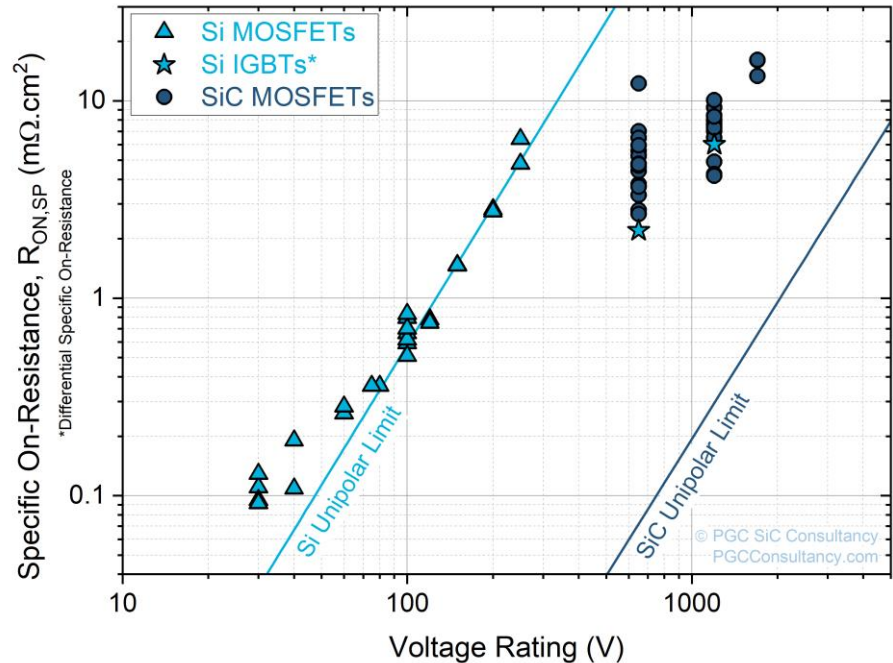
Enabling 800 V Architectures

- Automotive industry drive to move from 400V towards a battery DC link 800V.
 - With the same power, the lower the current through the **cables, the lower the power loss**
 - reduce the diameter of the power cables,
 - save installation space, reduce the cost of cables,
 - reduce the overall mass.
 - **Smaller, lighter motors** due to the reduction of copper windings, and thus the efficiency of the motor drive is improved.
 - When charging, the charging system needs to provide a voltage that matches the battery. When the battery voltage goes up, the **charging power will be increased and thus shortening the charging time.**

Therefore, to satisfy the high battery DC link voltage requirement, **1200V devices** need to be employed.

Automotive Applications Requirements

The main power devices in the inverter are currently Si IGBTs or SiC MOSFETs.

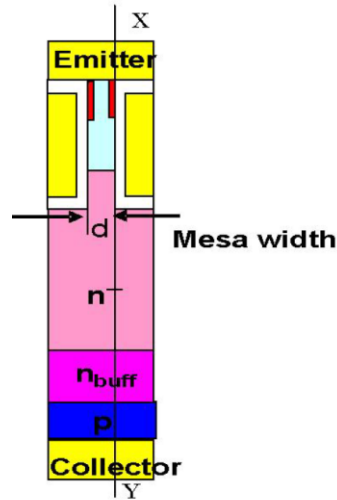
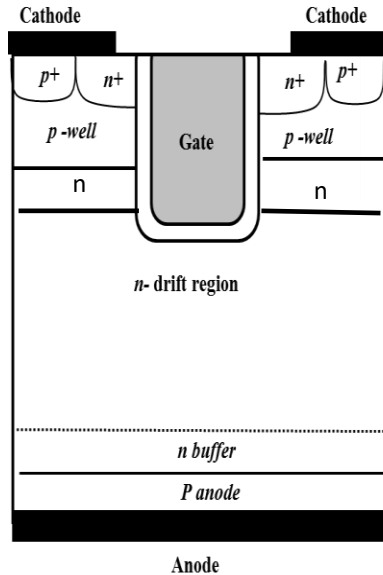


Si IGBT Developments

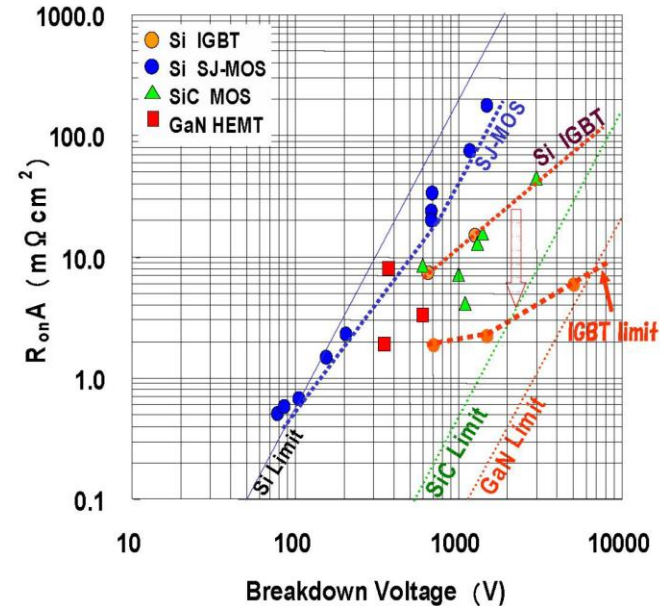


- Si IGBTs:
 - High Power Density
 - Highly reliable technology
 - Cost effective
- Potential Improvements
 - Better material/wafer utilisation (wafer thinning and larger wafer sizes up to 12inch)
 - Controllability through structure optimisation
 - Reverse Conducting IGBT

The conventional Si Trench IGBT



Narrow mesa structures (<100nm)



- Very narrow mesa structure results to very high injection efficiency and lower switching losses
- Short circuit capability has to be considered.

The conventional IGBT – narrow mesa technology

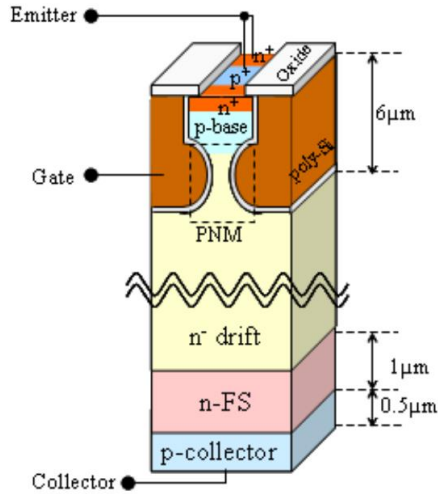
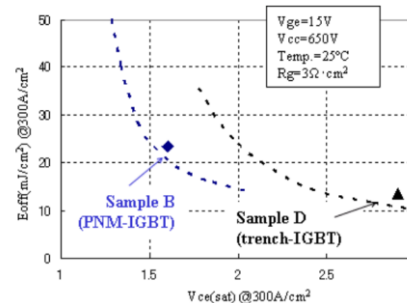
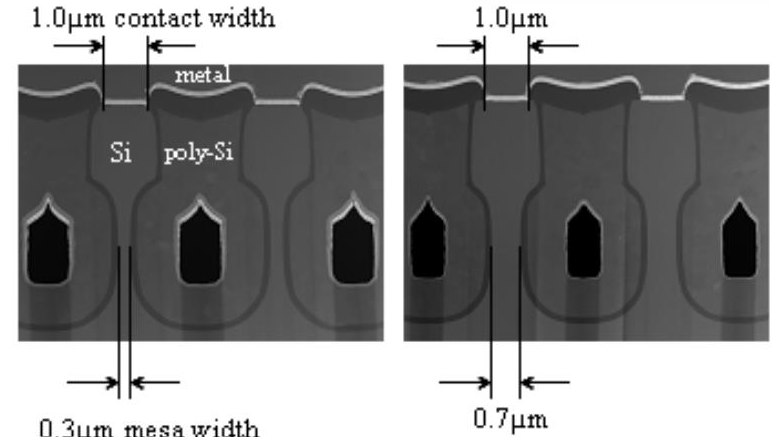
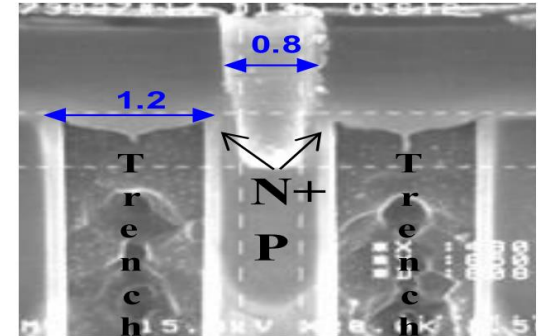
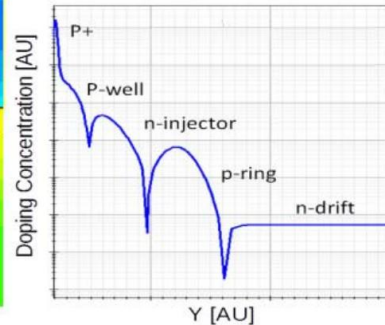
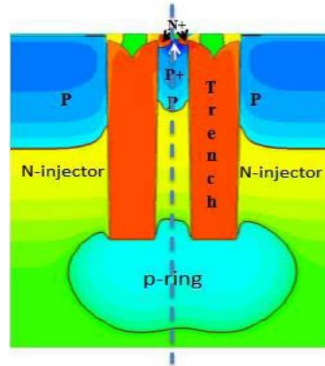
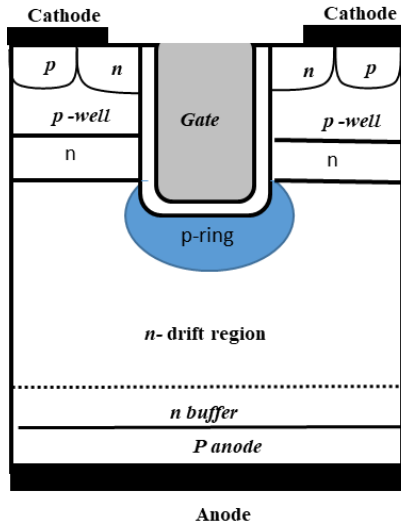


Fig.2 Schematic 3D view of a PNM-IGBT

- Very narrow 30nm mesa opening offering point injection enhancement
- Contact area remains sufficient for fabrication purposes.

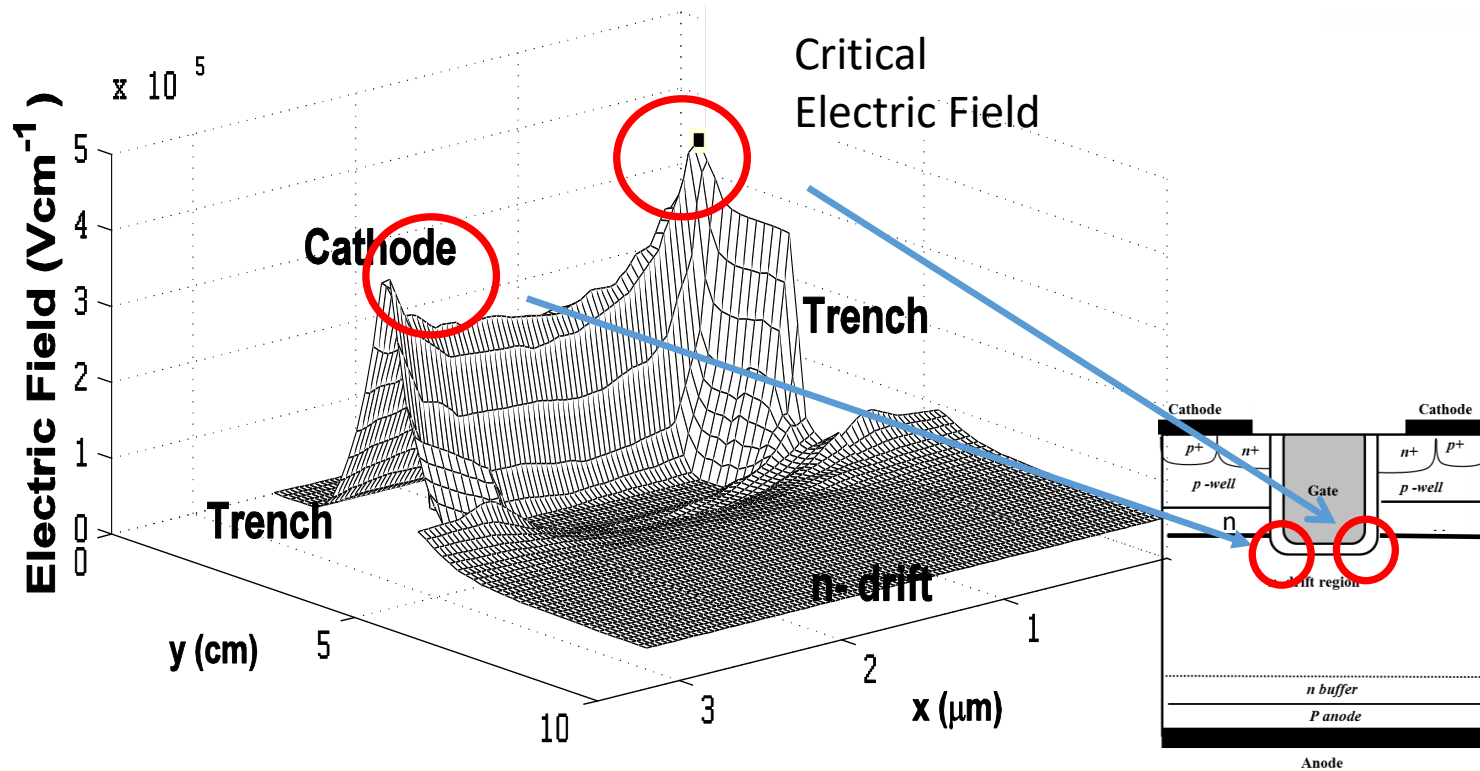


The p-ring IGBT

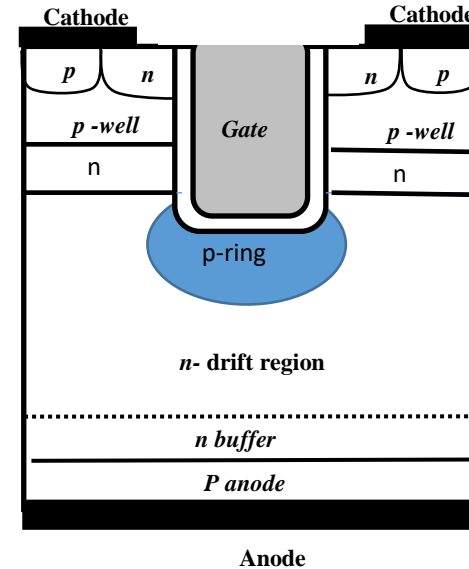
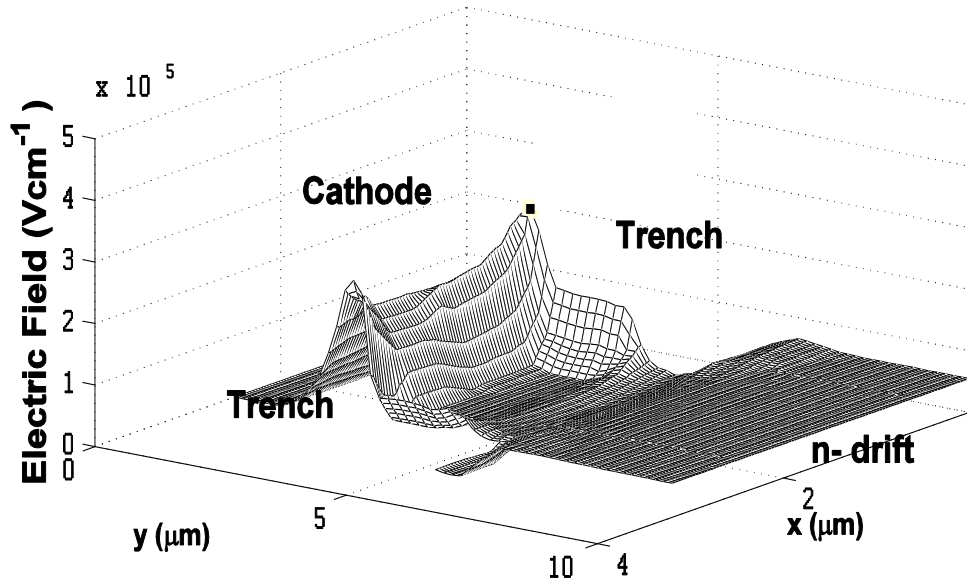


- p-ring achieved by implantation and diffusion and requires no additional masks
- The p-n regions help to distribute the field more uniformly across the cathode side
- 20% reduction in on-state losses without compromising the switching performance or the breakdown rating at both RT and 125 °C

The IGBT Electric Field Distribution @ $V_a=240V$

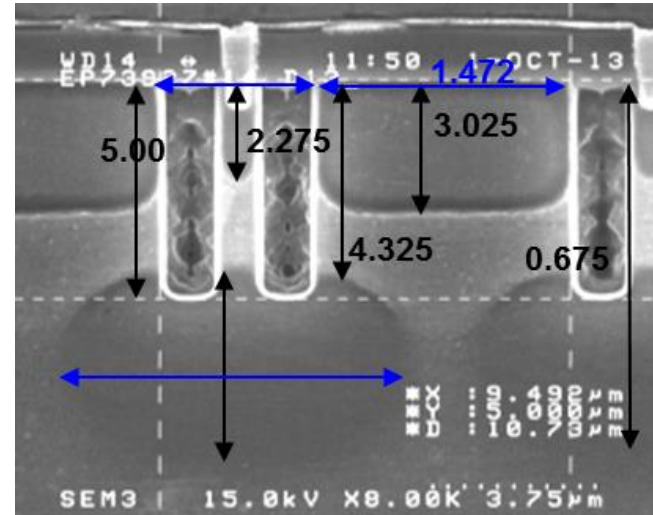
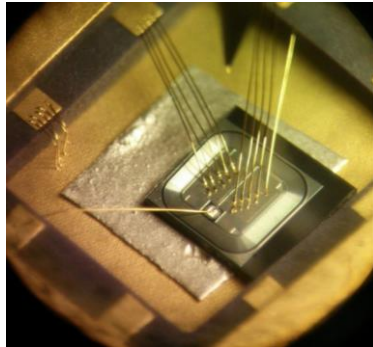
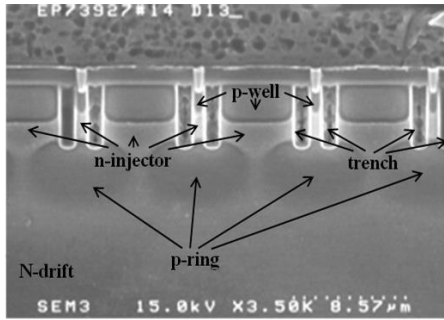


The p-ring IGBT Electric Field Distribution @1.2kV



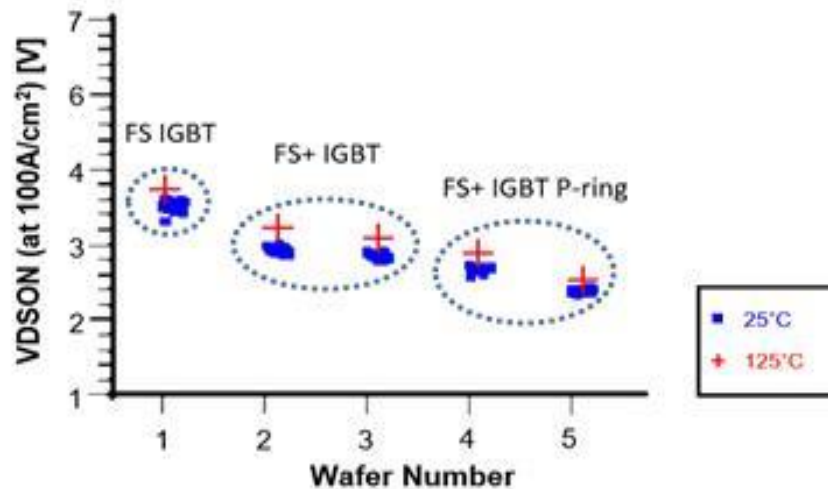
- Improvement in breakdown and the long term reliability: reducing the high electric fields peaks at the bottom or corner of the trenches oxide.

SEM Images of the p-ring IGBT



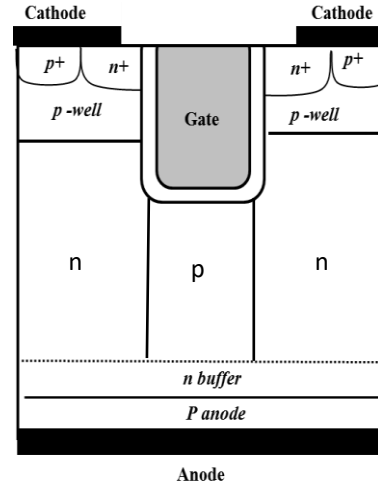
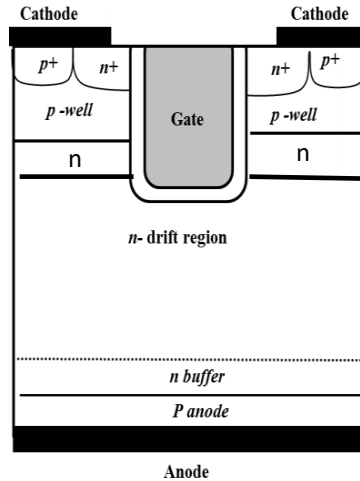
On state characteristics of the IGBT and the p-ring IGBT

On state voltage drop @100A/cm²



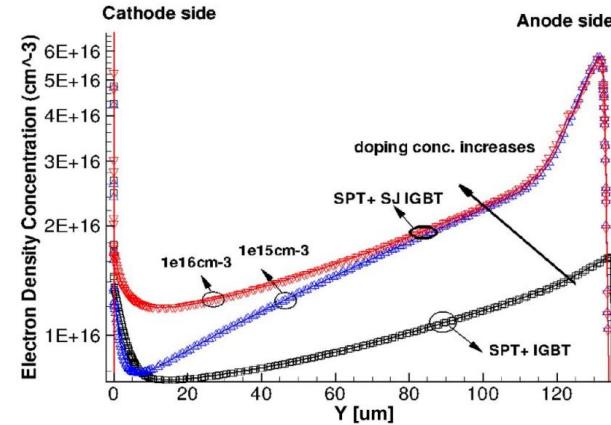
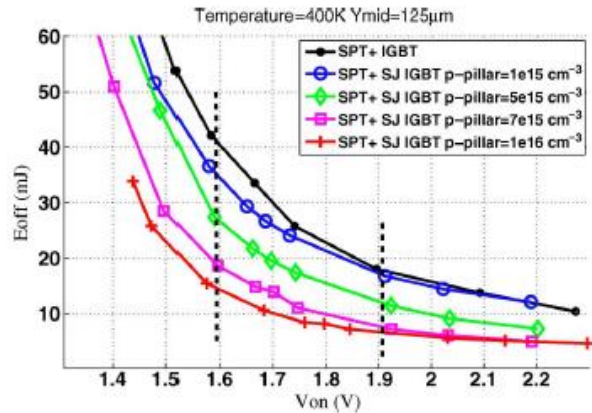
Up to 15% improvement
in the on-state device
performance

Si SuperJunction IGBT



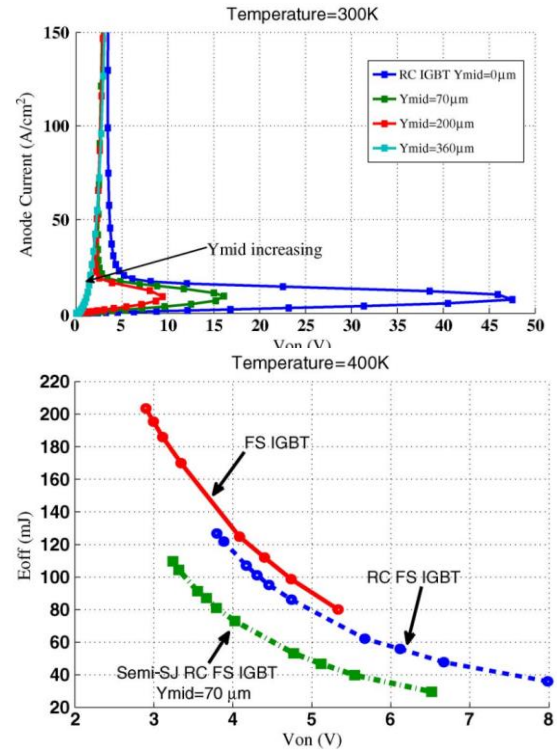
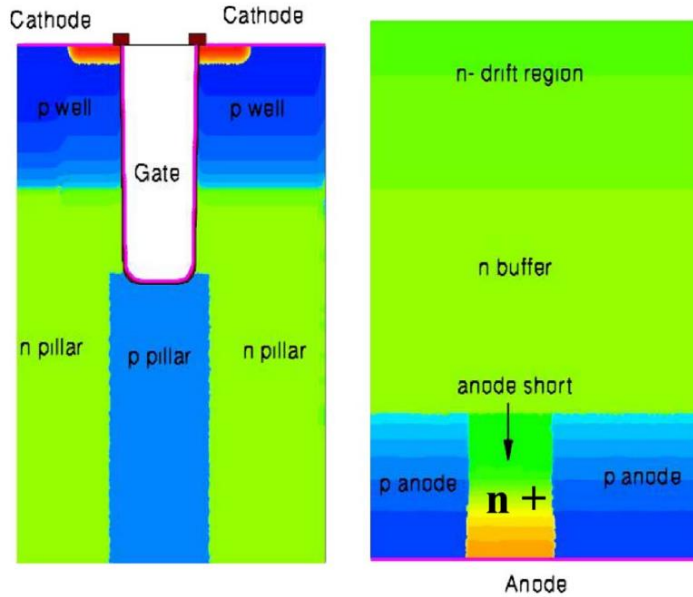
- The disconnected p column acts as deep collector of holes from the anode end of the drift region, thus increasing the turn-off speed.
- The SJ IGBT offers minimal drift length (for 1.2 kV this is just below 100 μm) - 20% cut from the conventional structure.

The technology curve: 1.2kV SuperJunction IGBT

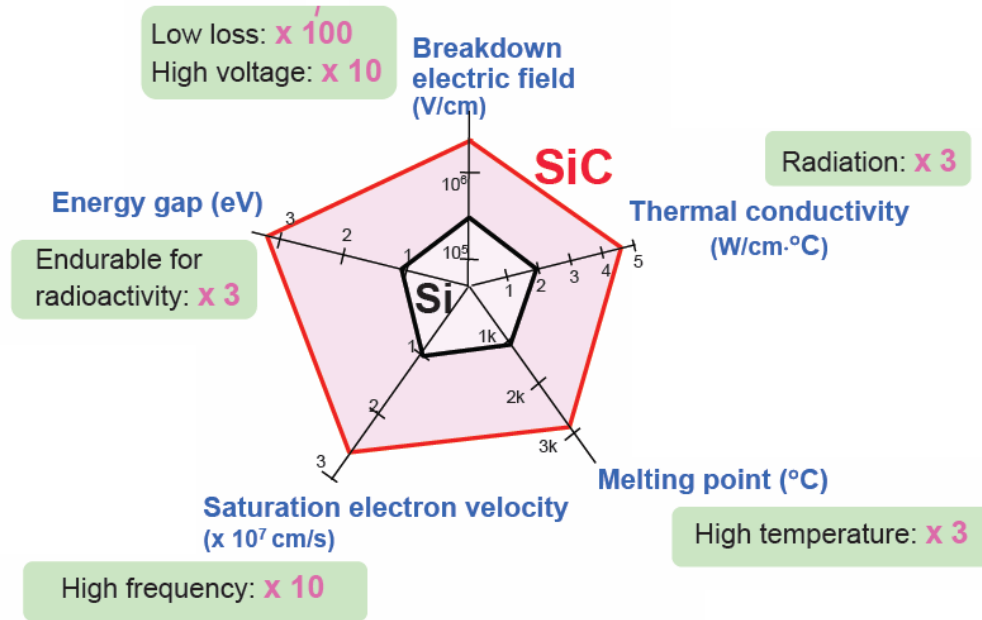


- The device can cut the on-state losses by 20% and the turn-off losses by almost 50% compared to a conventional structure.

Reverse Conducting IGBT



Properties of SiC compared to Si



Why Silicon Carbide?



- 9x Higher Critical Electric Field can be used to:
 - Produce **high voltage** solutions
 - Drive up **switching speeds**, reducing **converter size**
 - Drive up converter **efficiency**
 - Or a combination of all three.
- 2.5x greater thermal conductivity and 3x wider bandgap
 - Improved **thermal performance**
 - High **maximum operating temperature** (packaging allowing)
- Like Silicon:
 - **Freestanding SiC substrates** can be produced.
 - It can be oxidised to form **SiO₂**

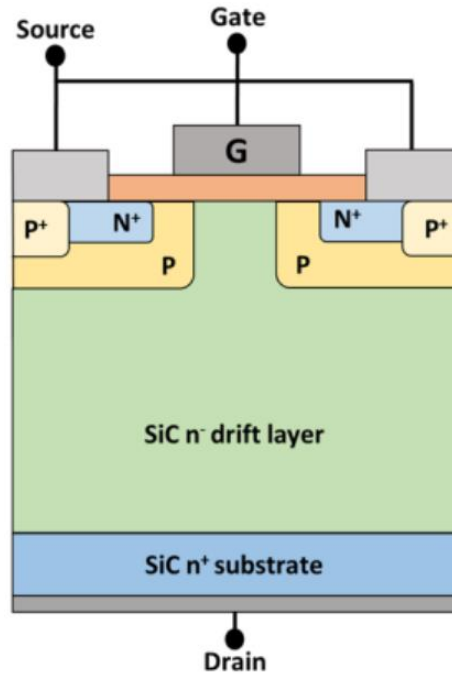
All figures compared to Si

Performance of SiC MOSFETs

- For the 1.2kV rating, the channel resistance contributes 40% of the R_{dson}
- SiC MOSFET have strong positive temperature coefficient
- SiC MOSFET have a good body diode
- E_{rec} are very low and don't increase much with temperature.
- Challenges
 - Low channel mobility
 - No suitable HT package materials
 - Gate Oxide reliability issues
 - Short circuit Performance

Silicon Carbide MOSFET

- Commercial planar SiC Power MOSFET



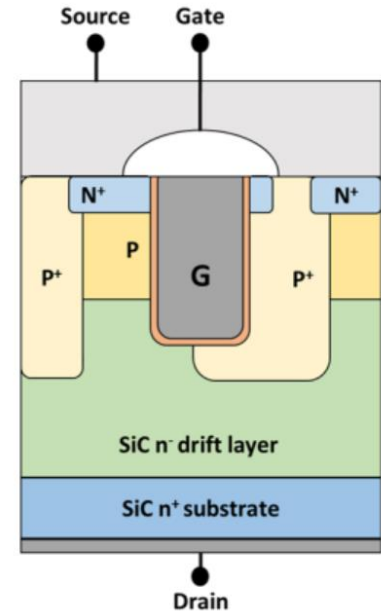
Many planar SiC MOSFETs are available today, Such as the STMicroelectronics structure.

- The channel is horizontal and quite resistive
- Body diode operation
- JFET effect

Silicon Carbide MOSFET

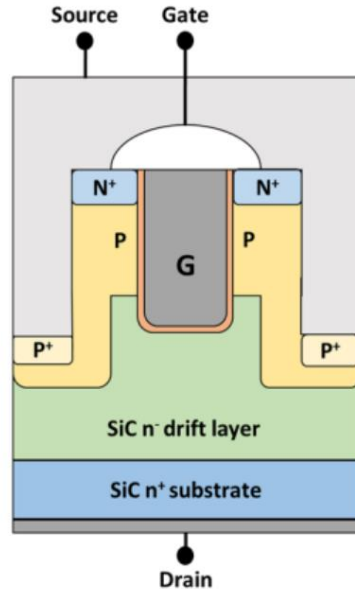
Infineon CoolSiC Trench MOSFET

- The channel is vertical with better mobility values.
- The trench MOSFET removes JFET region, however one side conduction channel along the trench wall.
- Deep P-regions on every trench to lower the electric field strength across the gate oxide.



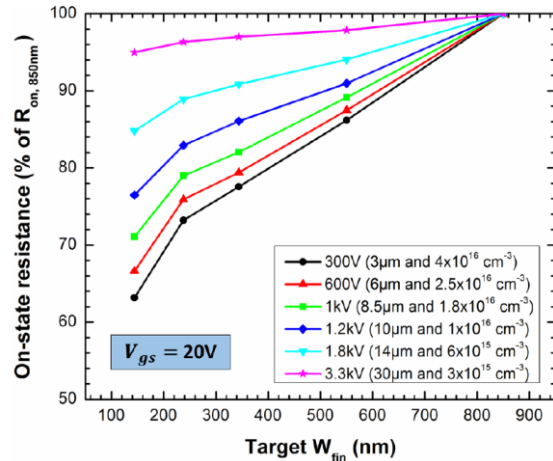
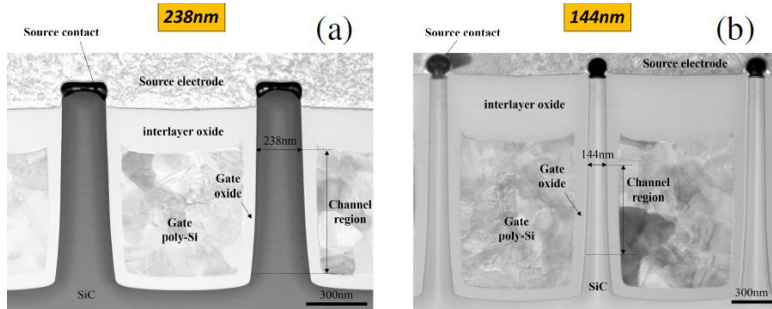
Silicon Carbide MOSFET

Rohms Double Trench MOSFET



- The trench MOSFET removes JFET region, and two side conduction channels along the trench wall.
- Deep p-layers to protect the gate oxide
- Source connected trench every other trench to enhance short-circuit ruggedness and to protect the gate oxide.
- On-state resistance improved by 50% and input capacitance down by 35%.

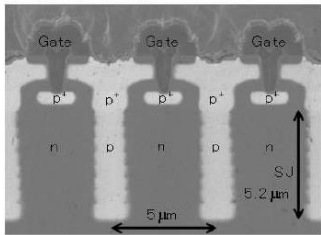
Silicon Carbide FIN MOSFET



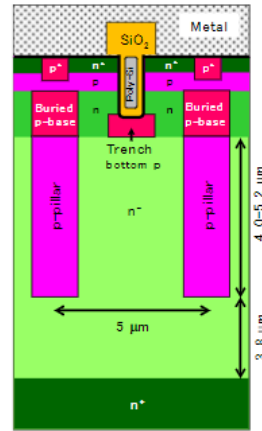
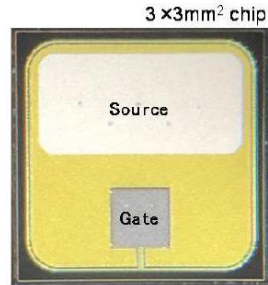
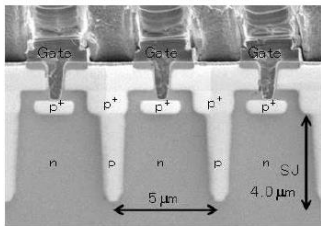
- The FinFET effect can overcome the low channel mobility.
- The structure is limited by the need for ultranarrow bodies between ~ 150 and 30 nm.
- This effect is more prominent for voltage ratings below ~ 1 kV where the drift resistance is relatively low compared to R_{ch} ; its impact fades away above 1.8 kV.

SJ SiC MOSFET

(a) Multi Epi



(b) Trench-filling Epi



- SJ concept is applied in the drift of the SiC MOSFETs
- The R_{onA} at HT is decreased by the SJ structure due to small drift resistance
- 1.2kV devices demonstrated.

Fig. 3: Cross-sectional SEM micrograph and photograph of the fabricated semi-SJ devices.

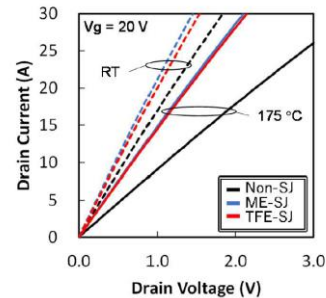
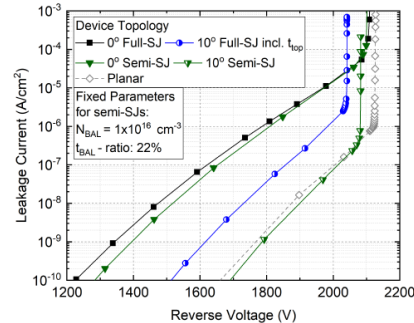
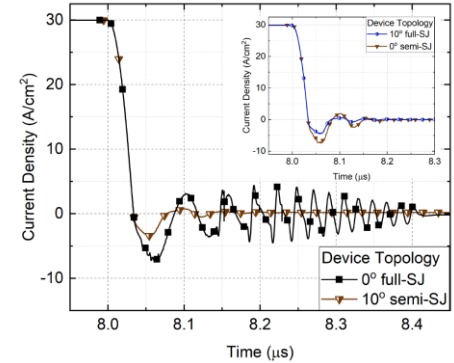
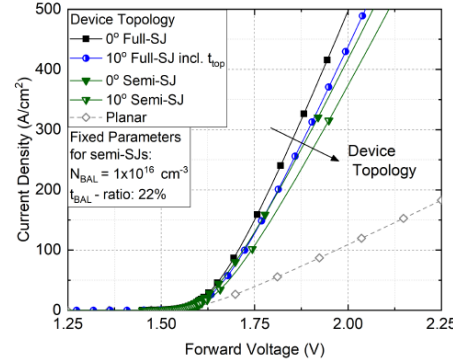
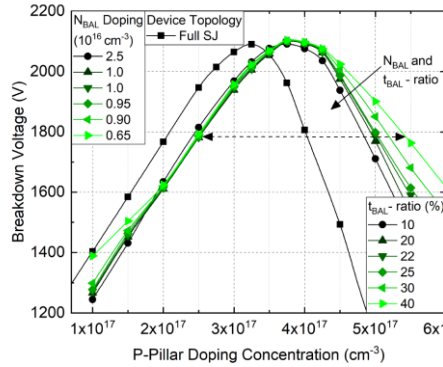
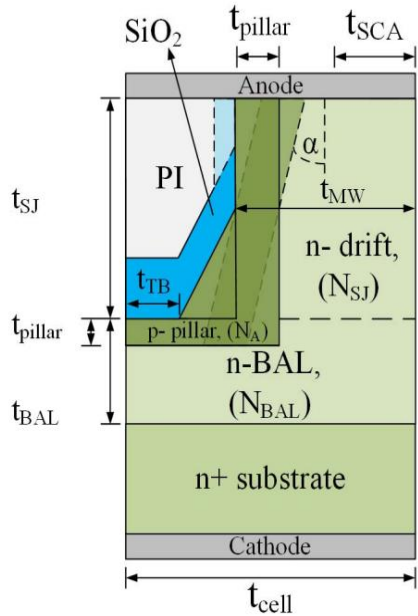


Fig. 4: I_D-V_D characteristic for $V_g = 20V$ at RT and 175 °C.

Semi-SJ SiC structures with angled side wall

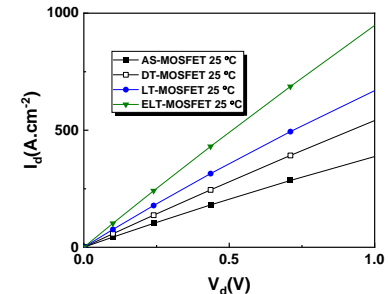
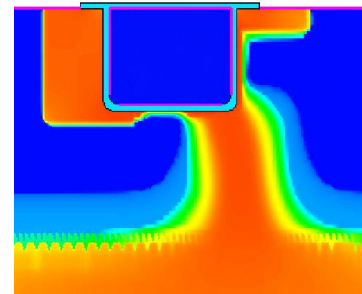
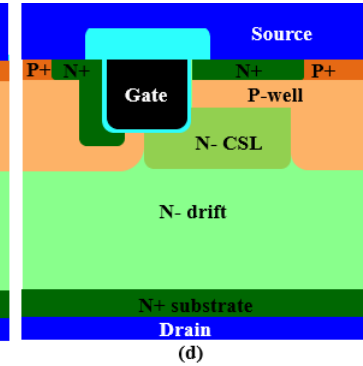
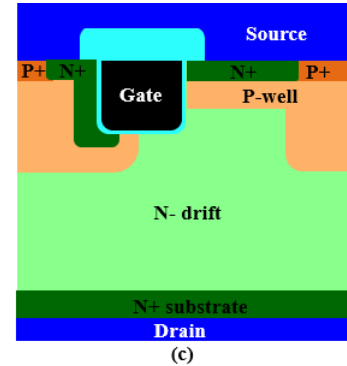
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- P-pillars are created through implantation into both the trench sidewalls and trench bottom
- Improved Process robustness against breakdown and performance improvement.
- Widens the implantation window by 34%, while maintaining a VBD and a $R_{ON,SP}$ comparable to a vertical full-SJ.
- Reduces the peak I_{RR} by 50%

Hybrid-Channel SiC Trench MOSFET

- The trench IGBT removes JFET region, and two side conduction channels along the trench wall.
- Deep p-layers to protect the gate oxide from high electric fields
- On-state resistance improved by 30% for the same blocking capability.



The Power of Silicon Carbide



SiC MOSFETs run hotter, switch faster and waste less power than Si IGBTs.

All of which lead to **Smaller, lighter converters**



Source: Rohm



ROHM supplies Full SiC Power Modules to Formula E racing team Venturi

Driving down SiC costs



SiC costs remain high compared to Si technology

Four key factors will drive down costs in the coming decade:

- **Larger area substrates:** adopting 8" / 200 mm wafers.
- **Incremental device/process improvement:** driving die size reduction.
- **Incremental yield improvements:** reducing substrate defect densities; improving fabrication methods.

Conclusions



- The automotive industry is shifting towards the 800V battery DC link Voltage
- Si IGBTs and SiC MOSFETS are the current two competing technologies to deliver this power.
- IGBTs are continually improving despite the Si material limitations and absence of body diode
- SiC MOSFET is establishing its self as the device of choice. However the device reliability issues and cost still limit its full potential.

Thank you!